



## SMALL-SCALE VACUUM INSTALLATION FOR FILM DEPOSITION BY MAGNETRON SPUTTERING AND THERMAL EVAPORATION

# MVU TM MAGNATIS 01

### Purpose:

Deposition of metal films, resistive materials and dielectrics.

### Special characteristics:

- Magnetron sputtering device - 1 pc.;
- Thermal evaporator – 1 pc.;
- Substrate processing in one technological cycle (single-sided processing):  
Ø 100 mm –4 pcs.;
- Periodical quarter-turn of substrate holder;
- Microprocessing control system;
- Oil-free pumping system (turbomolecular pump 300 l/h);
- Consumed power not more than 4,5 kW;
- 2,5 m<sup>2</sup> area per one installation.

